Cylindrical Titanium Sputtering Target TA1 Pure Zirconium Material

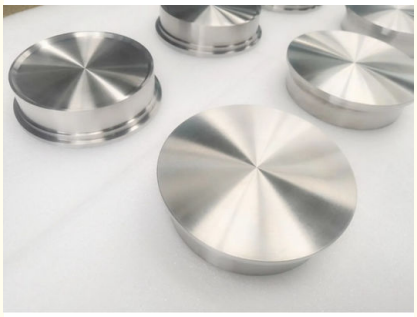
Our Product Introduction

Basic Information

- Place of Origin: China
- Brand Name: N/M
- Certification: ISO9001:2015 certification
- Model Number: CDX-20220331C
- Minimum Order Quantity: 10 piece
- Price: Negotiable
- Packaging Details: plywood case
- Delivery Time: 5-35 working days
- Supply Ability: 50000KG/month

Product Specification

- Name: Titanium Sputtering Target High Purity Titanium Target
- Key Words: Titanium Sputtering Target
- Application: Coating, Electronics Industry
- Grade: Gr1 TA1 Pure
- Density: 4.51g/cm3
- Purity: 99.9%-99.999%
- Purity 1: 2N8-4N
- Material: Pure Zirconium, Pure Niobium (Nb) Target
- Highlight: **Cylindrical Zirconium Target**, **Pure Zirconium Sputtering Target**, **TA1 Niobium Sputtering Target**



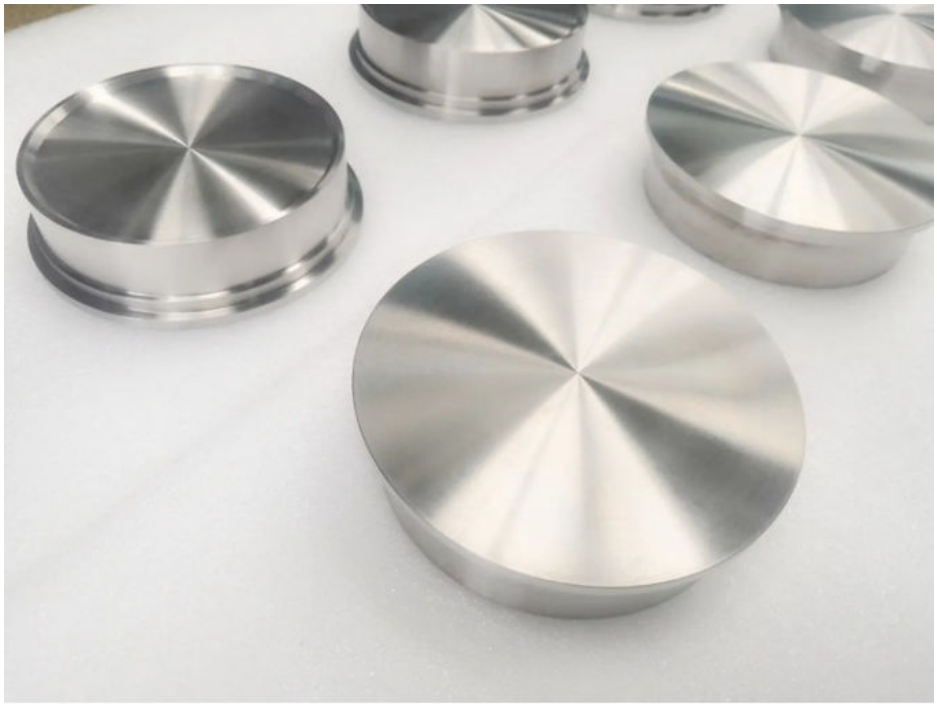
Our Product Introduction

Product Description

Diameter 60/65/95/100*30/32/40/45mm titanium aputtering target

Customized Titanium Target Titanium Round Target

product	Pure titanium (TI) target)
purity	2N8-4N
density	4.51g/cm3
Coating dominant color	Gold Blue / Rose Red / black
shape	cylindrical
General size	Diameter 60/65/95/100*30/32/40/45mm



Usually we will provide a quality inspection report like this with the goods, which shows the chemical composition and physical properties

宝鸡丞德鑫钛金属材料有限公司

Baoji Quality Metals Co., Ltd

质 量 证 明 书

Quality Certificate

证书编号（Certificate No.）：CDX20180331-01

合 同 号 Contract No.	产品名称 Description	牌 号 Designatio No.	批 号 Lot No/锭 号 Heat No.	状 态 Condition	规 格 Size(mm)	数 量 Quantity	产品标准 Product Standard	
/	Titanium bar	GR1	YTL20180126	M	16mm ×1000 mm	sample	ASTM B348	
室温力学性能 Tensile test	试验温度（℃） Test Temperature	抗拉强度 Rm（MPa） Tensile Strength	屈服强度 $Rp_{0.2}$（MPa） Yield Strength	断后伸长率 A(%) Elongation	断面收缩率 Z（%） Reduction of area	水压试验 Hydraulic pressure test	扩口试验 Expanding text	压扁试验 Flattening text
	Result	526	400	26	50	合格	合格	合格
其 它 Others	弯曲试验 t^0 Bend Test	低倍组织 Macrostructure	高倍组织 Microstructure	外形尺寸 Dimensional Inspection	表面质量 Visual Inspection	探伤检验 Ultrasonic Inspection	/	
	/	/	/	合 格	合 格	ok	/	

化 学 成 份 Chemical Composition （%）

Result	Ti	Al	Sn	/	/	/	/	Fe	C	N	H	O	Residual element	
	Remainder	/	/	/	/	/	/	0.11	0.06	0.02	0.001	0.07	≤0.10	≤0.30

编制：兰宝意 Prepared by

批准： Approved by

报告日期：2018 年 3 月 15 日 Report Date

宝鸡丞德鑫钛金属材料有限公司 BAOJI QUALITY METALS CO., LTD. 质量检验章

Supply titanium square target, titanium round target, titanium special-shaped target

Purity is one of the main performance indicators of the target,
because the purity of the target has a great influence on the performance of the thin film.

The main performance requirements of the target:
purity
Purity is one of the main performance indicators of the target, because the purity of the target has a great influence on the performance of the thin film. However, in practical applications, the requirements for the purity of the target are not the same. For example, with the rapid development of the microelectronics industry, the size of the silicon wafer has been developed from 6", 8" to 12", and the width of the wiring has been reduced from 0.5um to 0.25um, 0.18um or even 0.13um. Previously, the target purity was 99.995%. It can meet the process requirements of 0.35um IC, while the preparation of 0.18um lines requires 99.999% or even 99.9999% for the purity of the target material.
Impurity content
Impurities in target solids and oxygen and moisture in pores are the main sources of contamination for deposited films. Targets of different uses have different requirements for different impurity contents. For example, pure aluminum and aluminum alloy targets used in the semiconductor industry have special requirements for alkali metal content and radioactive element content.
density
In order to reduce the pores in the target solid and improve the performance of the sputtered film, the target is usually required to have a higher density. The density of the target affects not only the sputtering rate, but also the electrical and optical properties of the film. The higher the target density, the better the performance of the film. In addition, increasing the density and strength of the target allows the target to better withstand thermal stress during sputtering. Density is also one of the key performance indicators of the target.
Grain size and grain size distribution
Usually the target material is of polycrystalline structure, and the grain size can be in the order of micrometers to millimeters. For the same target material, the sputtering rate of the target with fine grains is faster than that of the target with coarse grains; while the thickness distribution of the thin film deposited by sputtering of the target with

smaller grain size difference (uniform distribution) is more uniform.

ZAMAYA Provide the most accurate data reports
Baoji Luox Quality Metals Co., Ltd.

+8613911115555 test@test.com titanium-part.com

GAOYA INTERSECTION, BAOTAI ROAD GAOXIN DISTRICT, BAOJI SHAANXI CHINA